Supplementary information

Robust topographical micro-patterning of nanofibrillar collagen gel by *in situ* photochemical crosslinking-assisted collagen embossing

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(1) Conventional collagen compression-based embossing and IPC-CE process

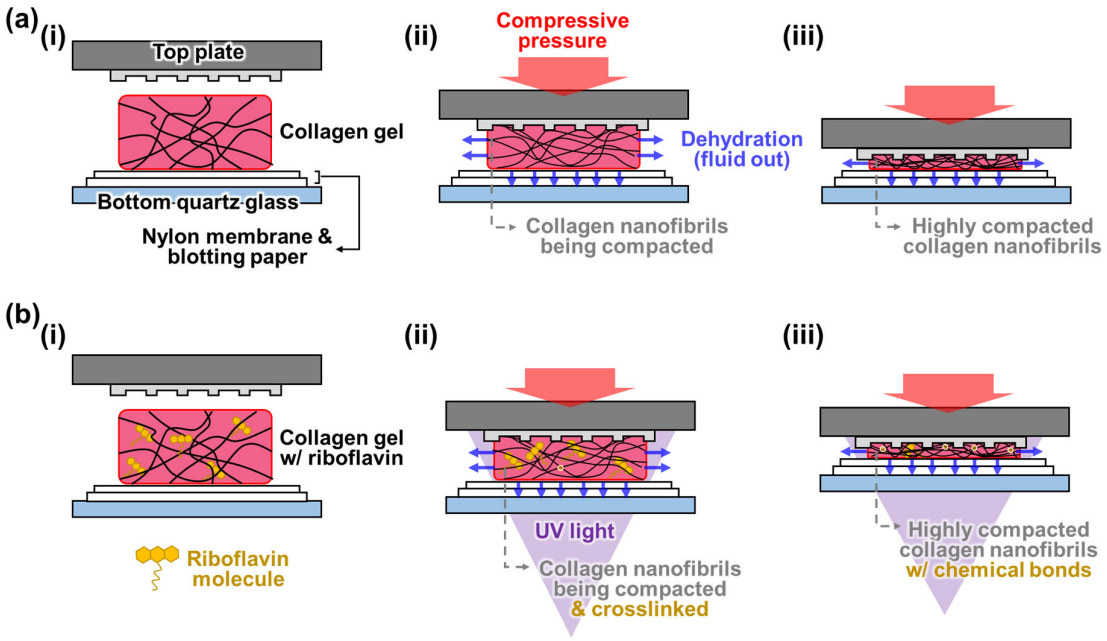

Figure S1. Schematic illustrations of (a) Conventional compression-based embossing and (b) IPC-CE process. Collagen gel (i) at initial, (ii) intermediate, and (iii) final stage of each process.

(2) Various sizes and shapes of micro-patterns

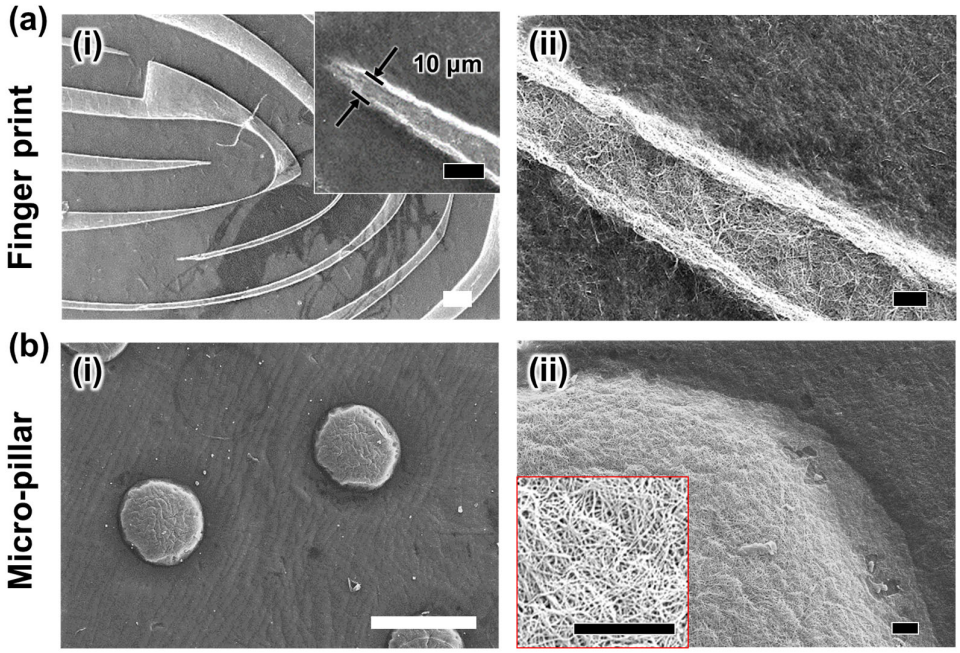

Figure S2. Various sizes and shapes of micro-patterns of IPC-CE construct. SEM images of IPC-CE construct with (a) fingerprint (~ 8–700 μm in width) and (b) micro-pillar patterns (~ 150 μm in diameter) at (i) low and (ii) high magnifications. White and black scale bars are 200 and 5 μm, respectively.